

	Hits	Search Text	DBs
1	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((mask or reticle or photo\$3mask\$4) same pattern\$4) and ((project\$4 or imping\$4 or bombard\$4) same (plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
2	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((project\$4 or imping\$4 or bombard\$4) same (plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	31	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 (methane or ethane or alkane)) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
4	34	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near9 (methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
5	0	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((mask or reticle or photo\$3mask\$4) same pattern\$4) and ((project\$4 or imping\$4 or bombard\$4) same (\$4beam or plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	USOCR

	Hits	Search Text	DBs
6	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near9 (methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask)	USOCR

	Hits	Search Text	DBs
7	28	((radiation or light or optical or projection or \$5lithographic) same (source or system or apparatus) same (substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3) same (pattern\$4 or mask or reticle or photomask)) and ((plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or laser or IAD or ion\$3assist\$4dep\$4 or EUV or DUV or \$5beam) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near14 (methane or ethane or alkane)) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	6	((("6252648") or ("20020000519") or ("6268904") or ("4987008") or ("6407385") or ("20020051124"))).PN.	US-PGPUB; USPAT

	Hit s	Search Text	DBs
9	128	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
10	85	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane) same gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
11	1	(projection near9 \$5lithograph\$4 near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
12	4	<p>(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>

	Hits	Search Text	DBs
13	2	<p>(projection near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>

	Hits	Search Text	DBs
14	6	(projection near9 (optical or system or apparatus)) and. ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	55	((light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3) same ((pattern\$4 near9 device) or mask or photomask or reticle)) and ((plasma or e\$3beam or (electron near4 beam) or beam or (electro\$3magnetic near6 field) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	29	((light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3) same ((pattern\$4 near9 device) or mask or photomask or reticle)) and ((plasma or e\$3beam or (electron near4 beam) or beam or (electro\$3magnetic near6 field) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	41	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	0	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitric near5 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	0	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitr\$4 near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	18	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitr\$4 near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	57	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus) same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitric near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	2	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus) same ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) near9 ((HNO\$2 or nitric) near8 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
23	111	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) near9 ((HNO\$2 or nitric) near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB